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Misaka, A.; Matsuo, T.; Sasago, M.;

VLSI Technology, 2002. Digest of Technical Papers. 2002 Symposium on , 11-13 June 2002

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2 Binary and phase shifting mask design for optical lithography

Liu, Y.; Zakhor, A.;

Semiconductor Manufacturing, IEEE Transactions on , Volume: 5 , Issue: 2 , May 1992

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3 Amplitude-phase-shift masks for projection lithography of submicron technology

Novosyadlyy, S.;

CAD Systems in Microelectronics, 2003. CADSM 2003. Proceedings of the 7th International Conference. The Experience of Designing and Application of , 18-22 Feb. 2003

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IEEE CNF

4 Investigation of half-tone phase shift mask with FIB and blue laser repair

Sang-Man Bae; Do-Hwa Lee; Hee-Mok Lee; Myung-Goon Gill; Bong-Ho Kim; Dong-Jun Ahn;

 VLSI and CAD, 1999. ICVC '99. 6th International Conference on , 26-27 Oct. 1999
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New Product, "Phase Shift Mask Measurement System for F2 Lithography".

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